

四重極質量分析器を用いたアミノ基表面修飾用表面波 Ar/NH₃ プラズマの
質量スペクトル計測

Optical Spectroscopy and Mass Spectrometry Measurements during
Amino-group Surface Modification of Nanoparticles Using
Surface-wave Excited Ar/NH₃ Plasma

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1. Introduction

Recently, due to their remarkable properties like oxidation resistance and high hydrophilicity, graphite encapsulated magnetic nanoparticles (GEMNPs) are a strong candidate to be implemented in novel drug delivery or virus detection systems. To improve the efficiency of this nanoparticles we propose a novel, fast and reliable functionalization method represented by low temperature plasma processing as an alternative to the traditional wet chemical methods. In the current work we study the mechanism of plasma processing by employing quadrupole mass spectrometry correlated with optical emission spectroscopy.

2. Experimental setup

In figure 1 the schematic representation of the plasma processing unit is shown. Surface wave plasma (SWP) is ignited in different mixtures of Ar and NH₃ by launching the microwaves through slot antennas in the stainless steel vacuum chamber.

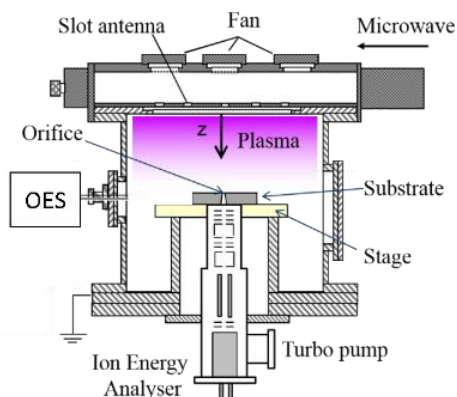


Fig.1 Schematic drawing of SWP device^[1]

3. Results and discussions

In our study, we use a mixture of Ar and NH₃ gases to investigate the optimum efficiency of the plasma

processing technique toward the amination of the GEMNPs. Previously we showed that the creation of NH radicals plays an important role for the amine group introduction. Therefore, in Figure 2 (a and b) the comparative plotting of the intensities of the emission lines of NH (336nm) and Ar (696.5nm) for different mixtures of NH₃ and Ar are shown. The highest intensity for NH and Ar lines seems to be when only 10% NH₃ is used in the gas mixture.

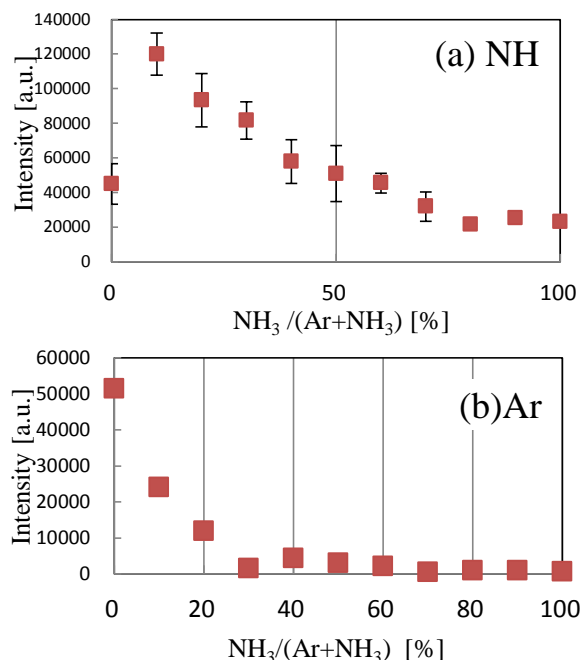


Fig.2 Emission intensity of NH₃/Ar plasma.
(a) NH (336nm); (b) Ar (696.5nm)

To prevent the dissociation of the NH₃ by the QMS the ionization energy was reduced until 18eV to assure that we are measuring only the neutrals from the plasma. Detailed information will be provided during the conference.

Reference

[1] Raman Bekarevich et al, J. Phys. D: Appl. Phys. 48, 045202, 2015